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Measurement of microstructural defect parameters in tungsten dichalcogenides: useful materials for the Li-ion battery applications

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ABSTRACT

Microstructural defect parameters like crystallite size (P), dislocation density (ρ) , rms strain $(\langle e^2 \rangle)^{1/2}$, stacking fault probability (α) , fractional change in interlayer spacing (g) and proportion of the plane affected by defects (y) are evaluated with the help of X-ray diffraction (XRD) studies for tungsten sulphoselenide, $WS_2 Se_x (0 \le x \le 2)$ compounds. These structural defect parameters are correlated with the compositional changes. The variation of conductivity with composition have also been correlated in terms of the structural defect parameters like P, ρ , $(\langle e^2 \rangle)^{1/2}$, α , g and γ . Room temperature electrical conductivity measurements indicated the semiconduction behavior in WS_{2,x}Se_x(0≤x≤2) compounds. Microstructural defect parameters are corelated with the electrical conductivities. © 2016 Trade Science Inc. - INDIA

KEYWORDS

Tungsten sulphoselenide; Microstructural defect parameters; Electrical conductivity.

INTRODUCTION

Layered transition metal dichalcogenides (TMDs), MX_2 (M = Mo, W; X = S, Se), have been the subject of a great deal of investigation in the recent years^[1-8]. TMDs are anisotropic materials having strong bonding within the layers and weak van der waals interactions in between the layers^{[9-} ^{12]}. Tungsten disulfide (WS₂), as a typical TMD^[13], has garnered spectable interest for its unusual combination of properties and extensive applications in catalysis, photosensor devices, field-effect transistors, hydrosulfurization, hydrogen evolution reactions, tribological applications and lubricants^{[2-7,10-} ^{11,13}]. The graphene-like layered material WS₂ has been attracted great attention as promising anode materials for lithium ion batteries (LIBs) because of their unique layered crystal structure, which prefers ions and molecules for the intercalation^[14]. The underlying crystal structure of WS, is composed of three stacked atom layers S-W-S held together by van der Waals forces and is beneficial to sustain fast insertion/de-insertion of Li+ ion[4-7,14]. The graphene-like layered material WS, has higher theoretical capacity (433 mAhg⁻¹) than that of commercial graphite (372 mAh g⁻¹)^[14].

A significant amount of work on WS, and TMDs has been reported by a number of researchers^[1-14]. Hwang et[1] al reported room temperature modulation and ambipolar behavior of layered semiconduc-

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tor WS₂ in the transistor application. Wang and coworkers^[2] developed the WS₂-based counter electrodes for the dye-sensitized solar cells. Synthesis and electrochemical performances of layered tungsten sulfide-graphene nanocomposite as a sensing platform for catechol, resorcinol and hydroquinone have been reported by Huang et al^[3]. Pumera and Loo^[4] employed TMD (MoS₂ and WS₂) materials for sensing and biosensing devices. Zonghua et al^[5] found WS, as promising candidates for replacing noble metal catalysts due to their inexpensive cost and good electrocatalytic activities towards the hydrogen evolution reaction. MoS, and WS, nano objects have been studied in tribological applications by Maharaj and Bhushan^[6]. A fundamental study on the effects of exfoliation on the inherent electrochemical properties of TMD (MoS₂, MoSe₂, WS₂, WSe₂) materials have been carried out by Loo et al^[7]. Measurement of high exciton binding energy in the monolayer transition metal dichalcogenides WS₂ and WSe₂ have been investigated by Hanbicki and coworkers^[8].

Bhandavat and Fang et al investigated different morphologies and sizes of WS, as anode materials for LIBs[15-16]. Fang et al observed that the morphology of the as prepared WS, depends with the W/S ratio^[16]. They, with the X-ray absorption near-edge structure characterization showed that the d electrons of W deviate towards the Li (or S) atom during the discharge/charge process, thereby forming a weak bond between W and Li₂S (or S)^[16]. In order to avoid the disadvantages of rapid decay of capacity and poor rate capability of the W-S-W stacking sheets and low electronic conductivity in TMDs, Chen et al introduced a conductive spacer between WS₂ nanosheets through an efficient route^[17]. Wang et al. reported that layered MoS₂ intercalated by single-wall carbon nanotubes (SWCNT) can improve both stability and discharge capacity^[18]. A new composite consisting of graphene, poly ethylene oxide and exfoliated MoS₂, which showed high sepcific capacity and excellent high-rate performance for reversible Li⁺ storage, was designed by Xie and coworkers^[19]. Liu et al confirmed that the connectivity of intercalation of SWCNT and CuO in WS₂, with the discharge and charge specific capacities and electrochemical reversibilities of LIBs, are associated with the structural stability of the electrode materials^[20]. The degradation of the specific capacities of LiMn₂O₄ spinel, a promising candidate as cathode material in LIBs, was attributed to lattice defects^[21] by Kaiya et al. By constructing a simple Sn-Li battery system, Hirai et al investigated the effects of the volume change associated with the formation of Li–Sn compounds on the electrode potential from the viewpoint of the Gibbs free energy and associated elastic-strain energy^[22]. Wei group investigated the doping of atomic vacancies in the monolayers of tungsten disulfide by density functional theory calculations^[23]. Their results revealed that the atomic vacancy defects affect the electronic and optical properties of the tungsten disulfide monolayers. The strongly ionic character of the W-S bonds and the nonbonding electrons of the vacancy defects result in spin polarization near the defects.

Despite of all these recent progresses on the TMD (MoS₂, MoSe₂, WS₂, WSe₂) materials, there are many gaps in our understanding of the fundamental interactions which lead to the striking optical and electronic properties of these semiconducting materials. One very important espect of these materials are defect properties like crystallite size, rms strain, dislocation density, stacking faults, fractional change in interlayer spacing and the proportion of the planes affected by defects, which profoundly influence the electronic and optical properties of these materials. Very less work has been explored with these issues on WS, and WS, $Se_{\cdot}(0 \le x \le 2)$ materials. However, these defect properties of WS₂ and WS₂, Se_x ($0 \le x \le 2$) play a vital role in governing their suitability in the derired applications. The present paper addresses the X-ray line profile analysis of $WS_{2-x}Se_x(0 \le x \le 2)$ compounds in order to investigate the crystallite size, rms strain, dislocation density, stacking fault probability, fractional change in interlayer spacing and proportion of the plane affected by defects.

EXPERIMENTAL DETAILS

The WS_{2-x}Se_x($0 \le x \le 2$) compounds were synthesized directly from the elements and the method of preparation is similar as reported earlier^[11]. Appro-



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priate amounts of the powdered elements were weighed accurately to produce the desired composition, mixed intimately to prepare a homogenous mixture, placed inside a quartz tube, which was sealed in vacuum and placed inside a furnace. The powder mixtures were heated slowly up to 400°C and kept for 72 h followed by heating at 750°C for 48 h and finally at 1000°C for 40 h. Then, the furnace was slowly cooled down to room temperature.

In order to measure the XRD the ingots were ground properly at room temperature. XRD of these powdered samples were carried out on a Philips 1729 diffractometer using monochromatic CuKα₂ radiation. Accurate lattice parameters were obtained by the least square method. Earlier studies on the effect of crystallite size by the line profile of WS. have shown that the crystallite size affects the low angle region of the profile whereas the high angle region remained unchanged. The intensity profiles of the (002) reflection in the X-ray diffractograms of all the samples were recorded from which structural parameters like dislocation density, root mean square strain and layer disorder parameters were calculated adopting a single line technique similar to that described earlier[11].

The physical significance of variance or the second moment about the mean, defined by

$$\mathbf{W} = \frac{\int (\boldsymbol{\theta} - \overline{\boldsymbol{\theta}})^2 \mathbf{I}(\boldsymbol{\theta}) d\boldsymbol{\theta}}{\int \mathbf{I}(\boldsymbol{\theta}) d\boldsymbol{\theta}}$$

as a measure of line broadening due to crystallite size, strain, mistake and dislocations. Here θ is the diffraction angle, $\bar{\theta}$ is the centroid of X-ray line profile, $I(\theta)$ is the diffracted intensity at θ . Based on this variance of the line profile, $W(2\theta)$, can be written as^[9,10]

$$W(2\theta) = \frac{\lambda \Delta(2\theta)}{2\pi^2 P_v \cos \theta} + \frac{S\lambda^2}{\cos^2 \theta}$$

where
$$S = \frac{\langle e^2 \rangle - \beta_d^2 / \pi^2}{d^2}$$

 $\Delta(2\theta)$ is the angular range over which the intensity distribution is applicable, $\langle e^2 \rangle$ is the mean square strain, λ is the wavelength of the X-rays, θ is the Bragg angle and d is the interplanar distance. P_V is the apparent crystallite size, which is obtained by

the method of variance. The true crystallite size as determined by the method of Fourier analysis^[9], P_F and P_V are related as

$$\frac{1}{P_{V}} = \frac{1}{P_{F}} + \frac{\beta_{d}}{d}$$

where β_d is the integral width of the defect profile. Thus a plot of $W(2\theta)$ as ordinate versus $\Delta(2\theta)$ as abscissa by emphasizing the points corresponding to the tail, will be linear and the slope will give apparent crystallite size P_V and the intercept, $(\langle e^2 \rangle - \beta_d^2/\pi^2)/(\lambda^2/\cos^2\theta)$. Thus knowing the values of P_F and P_V the value of P_F can be obtained. The magnitudes of mean fractional change in the inter layer distance P_F in the direction of P_F and the fractions P_F in the direction of P_F and the fractions P_F in the direction of P_F and the fractions P_F in the direction of P_F and the fractions P_F in the direction of P_F and the fractions P_F in the direction of P_F and the fractions P_F in the direction of P_F and the intercept P_F in the direction of P_F and the fractions P_F in the direction of P_F and the intercept P_F in the direction of P_F and the intercept P_F in the direction of P_F and the intercept P_F in the direction of P_F and P_F in the direction of P_F in the

$$g = \frac{1}{\pi l} \cot^{-1}(\frac{\pi \Delta}{\beta_a})$$

$$\gamma = \frac{\beta_d}{\sin^2(\pi.l.g)}$$

where, l is the order of reflection, Δ is the measure of peak shift from the centroid of the diffraction profile. A dislocation is an imperfection in a crystal associated with the misregistry of the lattice in one part of the crystal with that in another part. The dislocation density (ρ) has been estimated^[25] using the relation

$$\rho = \frac{2(3 < e^2 >)^{1/2}}{bP_v}$$

where b is the Burger's vector.

Warren^[10] defined stacking fault probability (α) as probability of finding a deformation between any two successive layers. The average number of layers between faults is $1/\alpha$ assuming that the probability of a fault between any two layers is independent of the faulting between other layers. Thus α can be calculated using

$$-\left(\frac{dA_{n}}{dn}\right) = \frac{1}{P_{v}} + \frac{3\alpha ld}{c^{2}}$$

where $(\frac{dA_n}{dn})$ is the initial slope of the Fourier coefficient (A_n) obtained from Fourier analysis of X-ray

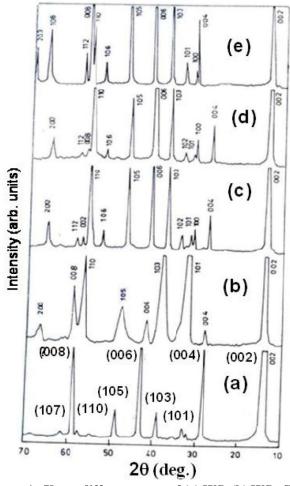
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diffraction profile versus order $(n)^{[10]}$, c is the lattice parameter in the direction of stacking and l the order of reflection.

The crystallite size anisotropy (P_F⁰⁰²/ P_F¹⁰³) for all these compounds was calculated by finding out the relative change in the true crystallite size (P_F) for 002 and 103 reflections. Room temperature electrical conductivity measurements were performed using a two probe method on compressed pellets. The compressed samples may involve oxidation barriers between the particles and some voids. Existence of air holes may also strongly affect the electrical properties. Therefore all the electrical measurements have been performed on sintered pellets.

RESULT AND DISCUSSION

Figure-1 shows the X-ray diffractograms (XRD) of $WS_{2x}Se_x$ (0 $\leq x\leq 2$) compounds. The XRD of WS_{2x} $_{x}$ Se $_{x}$ (0 \leq x \leq 2) compounds were thoroughly scanned for all the possible phases e.g., WS₂, WSe₃ W₃Se₄ etc. The peaks observed in the diffractogram in Figure 1(a) are assigned in terms of Miller-indices (hkl) considering a hexagonal crystal structure (space group P6₂/mmc) with the lattice parameters a = 0.315nm and $c = 1.235 \text{ nm}^{[26-27]}$. The diffractograms in Figure 1 for $WS_{2-x}Se_x$ (0 $\le x \le 2$) compounds showed good resemblance with one another, suggesting that even upon selenium substitution in WS₂, the structure of the host remains unchanged. The inter planer distance calculations corresponding to different planes are found to be in good agreement with the reported data^[26-27]. The most intense peak (relative intensity = 100%) lies at 0.6162 nm in (002) reflection. The maximum intensity of the (002) reflection indicates a strong orientation along the c-axis. The other (00*l*) reflections such as (004), (006) and (008) are of relatively much weaker intensity. The intensity variation for (100), (101) and (111) reflections do not show any definite trend towards composition for WS₂, Se_x($0 \le x \le 2$) compounds. The lattice parameters (a and c) of all these compounds well match with that of the reported lattice parameters on WS₂ $_{\rm v}$ Se $_{\rm v}$ (0 \leq x \leq 2) compounds^[28-30]. Figure 2A and 2B presents a schematic variation of lattice parameters (a and c) and a/c respectively with composition (x) for



 $\begin{aligned} & \textbf{Figure 1: X-ray diffractogram of (a) WS}_{2}\text{ (b) WS}_{1.5}\textbf{Se}_{0.5}\\ & \textbf{(c) WS}_{1.0}\textbf{Se}_{1.0}\text{ (d) WS}_{0.5}\textbf{Se}_{1.5}\text{ and (e) WSe}_{2}\text{ compounds} \end{aligned}$

 $WS_{2-x}Se_x(0 \le x \le 2)$ compounds. It shows that both a and c varies linearly with the composition. The variation of c/a with composition shows a maximum for $WS_{1.0}Se_{1.0}$ compound almost similar to as reported by Mentzen and Sienko^[28].

Figure 3 shows the crystallite sizes of WS_{2-x}Se_x($0 \le x \le 2$) compounds calculated on the basis of variance (P_v) as well as Fourier methods (P_F). Figure 3 indicates a lower value of crystallite size (P_v), calculated by the variance method, as compared to that of the Fourier method (P_F). Such a difference may be attributed to the fact that the size obtained by Fourier method represents the volume average of the crystallite-dimensions measured normal to the reflecting planes, whereas in the case of variance method, it is a measure of mean thickness given by E = V/A, where A is the area of the projection of the crystallite of volume V on the reflecting plane and

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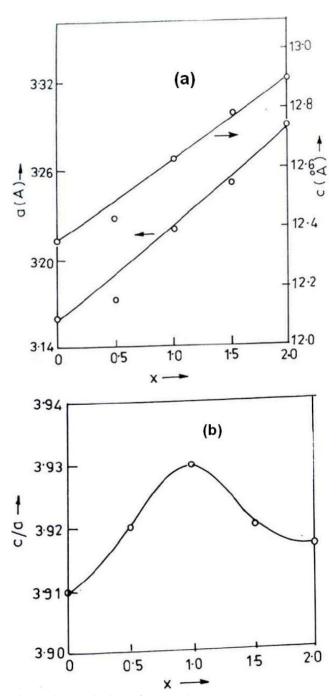


Figure 2 : Variation of (a) lattice parameters (a and c) and (b) c/a with composition (x) for $WS_{2-x}Se_x$ ($0 \le x \le 2$) compounds

is dependent on the defect concentrations^[31]. It appears from the data here that the size of the crystalite reaches a maximum value when the composition of sulphur and selenium is identical, ie. WS_{1.0}Se_{1.0}. In other compounds, with sulphur reach and selenium deficiency or vice versa, a decrease in the crystallite size is observed. In addition to the imperfection

of the crystallites as well as of lattice strain, dislocation and stacking faults are known to entribute towards the broadening of X-ray lines. Therefore the extent of intensity spread for each specimen is a measure of the nature and extent of lattice imperfections. Assuming that the defects are not related to each other, root mean square displacements (<e²>1/ ²) and dislocation density (p) were calculated by variance method for (002) reflection in WS₂ $Se(0 \le x \le 2)$ compounds. It is noted that with increasing selenium content in $WS_{2,x}Se_x(0 \le x \le 2)$ compounds both ($\langle e^2 \rangle^{1/2}$) and ρ decrease [Figure 4] gradually and attain a lowest value for WS_{1.0}Se_{1.0} and thereafter it showed an incresing trend. Such a behavior is just opposite to as observed in variation of crystallite size with composition. It is to be noted that the crystallite size values as determined by X-ray line profile analysis is the size of the crystallites which is surrounded by grain bondaries at the interfaces. With increase in the crystallite size value, the ratio of number of atoms lying in the grain boundaries region is smaller. Since the grain boundaries are formed by dislocation networks which also gives rise small inhomogenious strain, it is expected that the ($\langle e^2 \rangle^{1/2}$) and ρ values decrease with composition (x) and attain a minima at $WS_{1.0}Se_{1.0}$. Thus when

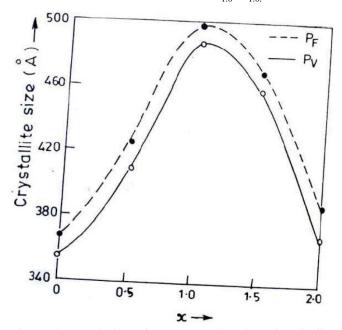


Figure 3 : Variation of the crystallite size of $WS_{2-x}Se_x$ ($0 \le x \le 2$) compounds by variance (P_v) and Fourier (P_F) techniques

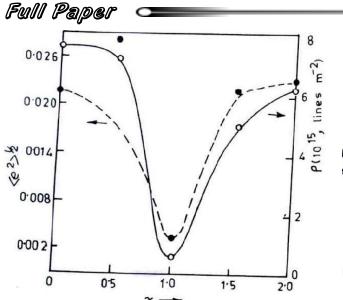


Figure 4: Variation of rms strain $(\langle e^2 \rangle^{1/2})$ and dislocation density (ρ) of $WS_{2,x}Se_x$ $(0 \le x \le 2)$ compounds

the sulphur and selenium are in the same proportion, strains are released more i.e more ordering is introduced in the sample. Any deviation from the composition introduced large amound of chaos. This is possibly due to breaking of the crystallites which leads to the corresponding increase in the rms strain as well as the dislocation density.

Figure 5 shows the variation of inter layer spacing (g) and the fractions of the planes affected by defects (γ) . It is obvious that g showed behavior just opposite to the crystallite size and with composition in $WS_{2-x}Se_x(0 \le x \le 2)$ compounds. It showed the presence of maxima at $WS_{1.0}Se_{1.0}$ suggesting thereby the presence of maximum layer disorder in this compound. It is also seen from the figure that γ in WS, is relatively much higher than that of WSe₂. It is also noted that γ decreases very rapidly up on slenium substitution in WSe, and attains a minima at WS_{1.0}Se_{1.0} and then it is slightly improved. This could be explained in terms of van der Waals forces which are operating in between the chalcogen layers. Since the van der Waals forces in between two selenium layers is much stronger than for the layers containing sulphur. Thus the probability of the planes affected by defects will increase as the amount of sulphur increases in $WS_{2-x}Se_x(0 \le x \le 2)$ compounds.

The variation of crystalite size anisotropy (P_F^{002}/P_F^{103}) and stacking fault probability (α) for WS_{2-x}Se_x(0 \leq x \leq 2) compounds are displayed in Figure 6.

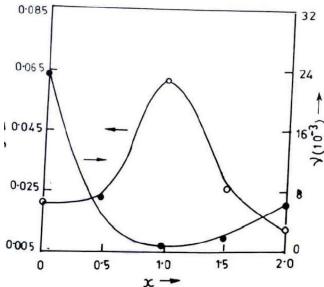


Figure 5: Variation of fractional change in interlayer spacing (g) and proportion of the plane affected by defects (γ) for WS_{2,x}Se_x (0 \leq x \leq 2) compounds

It is observed that both showed almost similar trend in their behavior. Initially both α and P_F^{002}/P_F^{103} increased almost linearly with composition (x) upto $WS_{1.0}Se_{1.0}$ and then decreased upto WSe_2 . The exact reason for the crystallite size anisotropy in measurements with polycrystalline aggregates is hard to found. Even if there exists a real crystallite shape anisotropy, this will be blurred the random orientation of the crystallites if all possible orientations

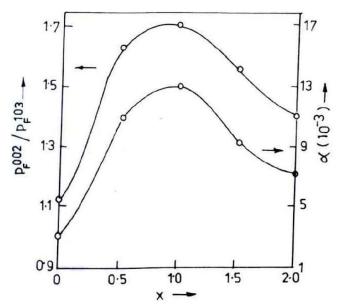


Figure 6: Variation of crystallite size anisotropy $(P_F^{002/}, P_F^{103})$ and stacking fault probability (α) for $WS_{2-x}Se_x$ ($0 \le x \le 2$) compounds

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TABLE 1 : Magnetic and electrical data of $WS_{2-x}Se_x (0 \le x \le 2)$ compounds

Compounds	$-\chi_{ m g} imes 10^{-6}$	Conductivity type	σ _{300K} (mho cm ⁻¹)
WS_2	0.35	p	2.0×10^{-4}
$WS_{1.5}Se_{0.5}$	0.31	p	2.7×10^{-5}
$WS_{1.0}Se_{1.0}$	0.28	p	1.4×10^{-6}
$WS_{0.5}Se_{1.5}$	0.17	p	1.0×10^{-5}
WSe_2	0.08	n	2.0×10^{-4}

have equal probability of occurence. If, however, there is a slight preference of some orientation, the average size in one direction may be different from other direction. The other reason for apparent crystallite size anisotropy may be due to the occurrence of stacking faults. As has been shown by Warren et al^[32] and Wagner et al^[33] the X-ray diffraction broadening of (111) and (200) reflections of FCC polycrystals are affected differently by the presence of stacking faults and the apparent crystallite sizes are different in two directions. The fact that crystallite size anisotropy as observed in thr present investigation is almost invariably accompanied by stacking faults indicates that preffered orientation plays an important role in giving rise this anisotropy. It appears from this data that the increasing faulting type introduced the breaking of crystallites in a particular direction. This may lead to the crystallite size anisotropy as observed in the $WS_{2,x}Se_x(0 \le x \le 2)$ systems. Thus based on observations from Figure 6 for α and $P_{_{\rm F}}^{~002}\!/\,P_{_{\rm F}}^{~103}$ respectively it is interesting to note that whenever α is low the size in that direction $(P_{\alpha\alpha})$ is high and vice versa.

Room temperature thermoelectric power measurements indicated that WS_2 and $WS_{2-x}Se_x(0 \le x \le 2)$ compounds possess p and n type conductivity respectively. The room temperature conductivity (σ_{300K}) data in TABLE 1 shows that σ in case of solid solution formation has decrease to some extent in comparison to pure MoS_2 and $MoSe_2$. These studies confirmed the semiconducting behavior of $WS_{2-x}Se_x(0 \le x \le 2)$ compounds.

CONCLUSIONS

X-ray line profile analysis has been carried out in order to estimate the microstructural defects like crystallite size (P), dislocation density (ρ) , rms

strain ($\langle e^2 \rangle$)^{1/2}), stacking fault probability (α), fractional change in interlayer spacing (g) and proportion of the plane affected by defects (γ) for WS, $_{v}$ Se $_{v}$ (0 \leq x \leq 2) compounds. It has been observed that P, $(\langle e^2 \rangle)^{1/2}$, γ and ρ are lowest for $WS_{1,0}Se_{1,0}$ while g, α and $P_{_{\rm F}}^{~002}/~P_{_{\rm F}}^{~103}$ showed a reverse trend. It is thereby concluded that the microstructural defects are relatively low in WS₁₀Se₁₀ and deviation from this composition in WS_2 , $Se_x(0 \le x \le 2)$ introduces more values of g, α and $P_{_{F}}^{~0\bar{0}\bar{2}\!/}\,\hat{P_{_{F}}^{^{103}}}$ and less values of P, $(<e^2>)^{1/2}$, γ and ρ. Room temperature electrical conductivity measurement indicated the lowest conductivity value in WS_{1.0}Se_{1.0} in comparison to other compounds in $WS_{2-x}Se_x(0 \le x \le 2)$. Thus the microstructural defect parameter calculations and their corelation with the electrical property of $WS_{2,x}Se_x(0 \le x \le 2)$ can guide the desired electrochemical properties of WS₂ based compounds for its applications in the Li ion battery.

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